



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of

Ni et al.

Application No. 09/586,530

Filed: May 31, 2000

For: ETCH ENDPOINT DETECTION

Docket No. LAM2P282

Group Art Unit: 1765

Examiner: V. Perez-Ramos

Date: February 3, 2003

1700
AF / 1765
PATENT #12/c
TA
REC 2/10/03

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, DC 20231 on February 3, 2003.

Signed:

Melinda M. Ward

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AMENDMENT

Commissioner for Patents and Trademarks
Washington, DC 20231

Applicants submit this paper in response to the Final Office Action dated December 2, 2002. Please amend this application as follows:

IN THE CLAIMS

1. (Three times Amended) A method for determining an endpoint for etching a layer, comprising:
 selecting a main etch endpoint; and, during etch,
 directing radiant energy at two or more wavelengths onto a layer to be etched;